



Application of Advanced Oxidation Processes

Guest Editors:

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Deadline for manuscript
submissions:

closed (31 March 2020)

Message from the Guest Editors

This Special Issue of *Processes* aims at covering recent progress and novel trends in the field of AOPs (advanced oxidation processes), including UV/H₂O₂, O₃, sulphate-radical oxidation, nanotechnology in AOPs, heterogeneous photocatalysis, sonolysis, Fenton, photo-Fenton, electrochemical oxidation, and related oxidation processes. Topics to be addressed in this Special Issue of *Processes* may also include the application of AOPs at various scales (laboratory, pilot, or industrial scale), the degradation of emerging contaminants in water and wastewater and pollutants in the gas phase, the quantification of toxicity in residuals, the development of novel catalytic material and of hybrid processes, including the combination of AOPs with other technologies, process intensification, and the use of photo-electrochemical processes for energy production. Authors with expertise in these topics are invited to submit their original manuscripts and review articles to *Processes*.





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Message from the Editor-in-Chief

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